

THERMOSTATIC GAS/LIQUID MIXTURE GENERATING SYSTEM FOR USE IN WAFER DRYING

ABSTRACT OF THE DISCLOSURE

5 A thermostatic gas/liquid mixture generating system for use in a wafer drying
process is disclosed, which includes: an inner tank; a first liquid supplying device,
which is used to supply liquid isopropyl alcohol (IPA) into the inner tank; a gas
supplying device, which is used to supply nitrogen (N_2) into the inner tank; an
exhausting device, which is used to exhaust a mixed gas of IPA and N_2 from the
10 thermostatic gas/liquid mixture generating system; an outer tank, which is spaced
apart from the inner tank; a second liquid supplying device, which is used to supply a
second liquid into the outer tank; a temperature controlling device, which is used to
control a temperature of the second liquid to an appropriate temperature range; and a
draining device, which is used to drain the second liquid out of the outer tank.

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Fig. 1